

AMENDMENTS TO THE SPECIFICATION

Please replace the Abstract of the disclosure, beginning on page 16 of the as-filed specification, with the following amended Abstract:

A method for manufacturing a substrate with a first plasma processing system having preconditioned components. The method comprises obtaining a component of a plasma processing system that has been coated with a film of material in a plasma processing chamber of a second plasma processing system different than the first plasma processing system, disposing the component in a plasma processing chamber of the first plasma processing system, disposing the substrate on a chuck in the plasma processing chamber of the first plasma processing system, and forming a plasma in a processing region within the plasma processing chamber of the first plasma processing system.

A clean copy of the amended Abstract is provided below:

A method for manufacturing a substrate with a first plasma processing system having preconditioned components. The method comprises obtaining a component of a plasma processing system that has been coated with a film of material in a plasma processing chamber of a second plasma processing system different than the first plasma processing system, disposing the component in a plasma processing chamber of the first plasma processing system, disposing the substrate on a chuck in the plasma processing chamber of the first plasma processing system, and forming a plasma in a processing region within the plasma processing chamber of the first plasma processing system.